grun that

P= 3000 0 hm·m, Me=0.12 mg/s, M=c S= = = eni(lle+lly) ni = es (Me+Mh) Ni = - 1 1.6x/-19x3000 (0.12+0.0045) ni = 0.365x/0/6 m-3 for Intrinsic Lemiconductor hit Pa Wtype ne.nh=ni ne.nh = (1.26304016)2 m6 (1) Si+P-0 N type (ē) ne = 1019/m3 : Mishing $P = \frac{1}{eneme} = \frac{1}{1.6\kappa/519\kappa/519\kappa0.12}$ [P = 5.2.08 ohm.m](Fi) h'- Borren + P type (hole) acceptos nh-ne = 20/0/9-10/9 - 10/9 8= -18.29 ohm.m)

18=18.29 ohm.m)

18 1.389 ohm.m)